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			U.S.	PATENT	DOCUMENTS				
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KR.		4,958,213	9-18-90	Eklund	, et aL	257	378		
		5,006,913	4-9-91	Sugaha	ra, et al.	25	167		
		5,060,030	10-22-91	Hoke, e	t al.	25	194		
		5,081,513	1-14-92	Jackson	, et al.	25	57		
KR		5,108,843	4-28-92	Ohtaka	, et al.	428	446		<u></u>
			U.S. PATENT	APPLICA	ATION PUBLICATIONS				
*EXAMINER INTIAL	PEP	DOCUMENT NUMBER	DATE		NAME	CLASS	. SUBCLASS	FILING IF APPRO	
KR		US 2002/0086497 A1	7-4-02	Kwok		438	424		
	US 2002/0090791 A1 7-11-02				et al.	438	.396		
	US 2003/0032261 A1 2			Yeh, et	al.	438	451		
KR		US 2003/0040158 A1	2-27-03	Saitoh		438	279		
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		,			iction Caused by Transistor EE, September 1999.				
		F. Ootsuka, et al., "A Hi Application." Internatio	ghly Dense, High nai Electron De	n-Perform vices Mee	ance 130nm Node CMOS ting, 23.5.1, IEEE, April 20	l'echnology 100.	for Large Scale S	System-on-	a-Chp
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KR		3,602,841	8-31-71	McGro	ddy	331	107 G			
<u> </u>		4,665,415	5-12-87	Esaki,	et aL	1257	190			
		4,853,076	8-1-89	Tsaur,	et al.	438	479			
		4,855,245	8-8-89	Neppl,	et al.	438	207	·		
KR		4,952,524	8-28-90	Lee, et	Lee, et al. 438 437					
101 =			U.S. PATE	NT APPLICA	ATION PUBLICATIONS					
*EXAMINER INITIAL	REP	DOCUMENT NUMBER	DATE		NAME	CLASS	8UBCLASS	FILING DATE IF APPROPRIATE		
V.P		US 2001/0009784 A1	7-26-01	Ma, et	ai.	438	197			
		US 2002/0063292 A1	5-30-02	Armstr	ong, et al.	257	367			
		US 2002/0074598 A1	6-20-02	Doyle,	et al.	257	345			
KR		US 2002/0086472	7-4-02	Roberd	ls, et al.	438	197			
			FOR	EIGN PATE	NT DOCUMENTS					
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		JP64-76755	03-1989	Japan						
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			U.S	. PATENT	DOCUMENTS			
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KR		5,134,085	7-28-92 '	Gilgen,	et al.	438	849	
		5,310,446	5-10-94	Konish	i, et aL	117	58	
		5,354,695	10-11-94	Leedy		438	411	
		5,371,399	12-6-94	Burrou	ghes, et al.	25	7 451	
KR	<u> </u>	5,391,510	2-21-95	Hsu, et	al.	43	8 301	
			U.S. PATENT	T APPLIC	ATION PUBLICATIONS	3		
•EXAMINER INITIAL	REP	DOCUMENT NUMBER	DATE		NAME	CLA88	SUBCLASS	FILING DATE IF APPROPRIATE
KR		US 2003/0057184 A1	3-27-03	Yu, et	al.	214	79	
RR		US 2003/0067035 A1	4-10-03	Tews,	et al.	257	333	
190								·
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		Shinya Ito, et al., "Mec International Electron A. Shimizu, et al., "Loc International Electron						
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			U.S.	. PATENT	DOCUMENTS			
*EXAMINER INITIAL	REP	DOCUMENT NUMBER	DATE		NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
KR		5,459,346	10-17-95	Asakaw	va, et al.	25	7 347	
		5,471,948	12-5-95	Burrou	ghes, et al.	433	9 93	
		5,557,122	9-17-96	Shrivas	tava, et al.	25	309	
		5,561,302	10-1-96	Candel	aria	25	7 24	
KR		5,565,697	10-15-96	Asakaw	ya, et al.	25	1 347	
			U.S. PATENT	APPLICA	ATION PUBLICATIONS			,
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		K. Ots, et al., "Novel I Devices Meeting, 2.2.1	ocally Strained C , IEEE, February	hannel Te 2002.	chnique for High Performs	ince 55nm	CMOS." Intern	ational Electron
		G. Zhang, et al., "A No IEEE Transactions on	ew 'Mixed-Mode' Electron Devices,	Reliability vol. 49, n	Degradation Mechanism I o. 12, December 2002, pp. 2	n Advance 151-56.	d Si and SiGe Bly	polar Transistors.
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			U.S	S. PATENT	DOCUMENTS			
•EXAMINER INITIAL	REP	DOCUMENT NUMBER	DATE		NAME	CLA58	SUBCLASS	FILING DATE IF APPROPRIATE
KR		5,571,741	11-5-96	Leedy		438	27	
]		5,592,007	1-7-97	Leedy		25	347	
		5,592,018	1-7-97	Leedy		25	1 619	
		5,670,798	9-23-97	Schetz	lna .	25	7 96	
KR		5,679,965	10-21-97	Schetz	ina	25	1 103	
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		Transistors." IEEE 19	mperature Depe 91 Bipolar Circu	nits and T	d Post-Stress Recovery of Fechnology Meeting 7.5, pp.	170-173.		
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KR		5,683,934	11-4-97	Candel	aria	42	8	151	
		5,840,593	11-24-98	Leedy		43	38	6	
		5,861,651	1-19-99	Brasen	, et al.	25	57	411	
		5,880,040	3-9-99	Sun, et	al.	42	38	769	
KR		5,940,716	8-17-99	Jin, et	al.	42	38	424	
			U.S. PATENT	T APPLICA	ATION PUBLICATIONS				
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		S.R. Sheng, et al., "Deg	radation and Rec	covery of	SIGE HBTs Following Re	diation an	d Ho	-Carrler Stress	ing." Pp. 14-15.
		Z. Yang, et al., "Avalar Transistors." Pp. 1-5.	ache Current Ind	uced Hot	Carrier Degradation in 2	200 GHz Si	Ge H	eterojunction l	Bipolar
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KR		5,940,736	;	8-17-99	Brady,	et al.		438	787		
		5,946,559		8-31-99	Leedy			438	157		
		5,960,297		9-28-99	Saki			438	424		
		5,989,978		11-23-99	Peidou	8		432	3 436		
KR		6,008,126	5	12-28-99	Leedy			438	3 667		
				U.S. PATENT	r applic.	ATION PUBL	ICATIONS				
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			l, et al., "Design of ems." 2003 IEEE (·			
		H. V Devi	Vurzer, et al., "Ann ces, vol. 41, no. 4,	ealing of Degrad April 1994, pp. 53	ed npn-T 33-38.	ransistors- M	echanisms a	nd Modeling	." IEEE Transa	ctions on E	lectron.
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			U.S	. PATENT	DOCUMENTS					
*EXAMINED INITIAL	REP	DOCUMENT NUMBER	DATE		NAMB		CLASS	SUBCLASS	FILING IP APPRO	
KR		6,025,280	2-15-00	Brady,	et al.		438	762		
		6,046,464	4-4-00	Schetzi	na		257	96		
		6,066,545	5-23-00	Doshi,	et al.		438	439		<u> </u>
		6,090,684	7-18-00	Ishitsu	ka, et al.		438	424	<u>.</u>	
KR		6,107,143	8-22-00	Park, e	t al.		438	296		
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		B. Doyle, et al., "Recov.	ery of Hot-Carri	er Damas						ce
		Letters, vol. 13, no. 1, J	anuary 1997, pp.	. 38-40.		•				
· · · · · · ·		H.S. Momose, et al., "A for Bi-CMOS." IEEE	nalysis of the Te	mperatur	e Dependence of H	lot-Carri	er-Induced D	egradation in	Bipolar Tra	ansistor
		for Bi-CMOS." IEEE	Transactions on	Electron l	Devices, vol. 41, no	. 6, June	1994, pp. 978	-y87.		
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			U.S	. PATENT	DOCUMENTS				
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KR		6,117,722	9-12-00	Wuu, e	et al.	438		<u></u>	
		6,133,071	10-17-00	Nagai		438	122		
		6,165,383	12-26-00	Chou		252	301.16		
		6,221,735	4-24-01	Manle	y, et al.	438			
KR		6,228,694	5-8-01	Doyle,	et al.	438	199		
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KR		6,246,095	6-12-01	Brady,	, et al.	25	7 411	
		6,255,169	7-3-01	Li, et a	.	438	3 264	
		6,261,964	7-17-01	Wu, et	al.	438	705	
		6,265,317	7-24-01	Chiu,	et al.	43	8 711	
KR		6,274,444	8-14-01	Wang	•	435	8 299	
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KR		6,281,532	8-28-01	Doyle,	et al.	251		
		6,284,623	9-4-01	Zhang,	et al.	438	424	
		6,284,626	9-4-01	Kim		438	3 433	
		6,319,794	11-20-01	Akatsu	, et al.	438	424	
KR		6,361,885	3-26-02	Chou		428	690	·
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KR		6,362,082		3-26-02	Doyle,	et al.		438	523	******	_
		6,368,931		4-9-02	Kuhn,	et al.	وارد برسود کو اید برسوس	438	359		
		6,403,486		6-11-02	Lou			438	694	•	
		6,403,975		6-11-02	Brunne	er, et al.		25	1 15		_
KR		6,406,973		6-18-02	Lee			438	3 416		
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KR		6,461,936	10-8-02	von Eb	renwall	438	424		
		6,476,462	11-5-02	Shimiz	u, et al.	25	0.2	· ·	
		6,483,171	11-19-02	Forbes	, et al.	125	1 627		
1		6,493,497	12-10-02	Ramdani, et al.		385	131	,	
KR		6,498,358	12-24-02	Lach, et al.		25	1 183		
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		6,506,652	1-14-03	Jan, et	al. '	438	303		
		6,509,618	1-21-03	Jan, et	aL .	25	7 413		
		6,521,964	2-18-03	Jan, et	al.	ର୍ଚ୍ଚ			
KR		6,531,369	3-11-03	Ozkan,	et aL	438	312		
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			U.S.	. PATENT	DOCUMENTS		-		
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE		NAME	CLA88	SUBCLASS	FILING DATE IF APPROPRIATE	
KR		6,531,740	3-11-03	Bosco,	et al.	25		<u> </u>	
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